

L Number	Hits	Search Text	DB	Time stamp
1	6060	438/525.ccls. 438/528.ccls. 438/586.ccls. 438/592.ccls. 438/595.ccls. 438/637.ccls. 438/675.ccls. 438/766.ccls. 438/770.ccls.	USPAT; US-PGPUB	2004/08/21 19:56
2	2658	(438/525.ccls. 438/528.ccls. 438/586.ccls. 438/592.ccls. 438/595.ccls. 438/637.ccls. 438/675.ccls. 438/766.ccls. 438/770.ccls.) and ((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp)	USPAT; US-PGPUB	2004/08/21 20:06
3	1659	((438/525.ccls. 438/528.ccls. 438/586.ccls. 438/592.ccls. 438/595.ccls. 438/637.ccls. 438/675.ccls. 438/766.ccls. 438/770.ccls.) and ((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp)) and (ion near implant\$8)	USPAT; US-PGPUB	2004/08/21 20:00
4	672	((438/525.ccls. 438/528.ccls. 438/586.ccls. 438/592.ccls. 438/595.ccls. 438/637.ccls. 438/675.ccls. 438/766.ccls. 438/770.ccls.) and ((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp)) and (ion near implant\$8)) and ((contact adj (opening hole via)) plug ((conduct\$6 metal) near via))	USPAT; US-PGPUB	2004/08/21 20:05
5	666	((438/525.ccls. 438/528.ccls. 438/586.ccls. 438/592.ccls. 438/595.ccls. 438/637.ccls. 438/675.ccls. 438/766.ccls. 438/770.ccls.) and ((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp)) and (ion near implant\$8)) and ((contact adj (opening hole via)) plug ((conduct\$6 metal) near via))) and (gate source drain sidewall spacer silicide (side adj wall))	USPAT; US-PGPUB	2004/08/21 20:04
7	371	((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp) same (ion near implant\$8) same ((contact adj (opening hole via)) plug ((conduct\$6 metal) near via)) same (gate source drain sidewall spacer silicide (side adj wall))	USPAT; US-PGPUB	2004/08/21 20:08
9	152	((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp) same (ion near implant\$8) same ((contact adj (opening hole via)) plug ((conduct\$6 metal) near via)) same (gate source drain) same (sidewall spacer silicide (side adj wall))	USPAT; US-PGPUB	2004/08/21 20:09
6	152	((438/525.ccls. 438/528.ccls. 438/586.ccls. 438/592.ccls. 438/595.ccls. 438/637.ccls. 438/675.ccls. 438/766.ccls. 438/770.ccls.) and ((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp)) and (ion near implant\$8)) and (sac (aligned adj contact))	USPAT; US-PGPUB	2004/08/21 20:45
11	1	20020079492.pn.	USPAT; US-PGPUB	2004/08/21 20:45
12	13	("4753896"   "5518946"   "5731236"   "5817562"   "5930634"   "6083816"   "6123766"   "6160271"   "6187676"   "6200840"   "6258675"   "6350665"   "6436818"   "2002/0001935"   "2002/0084482").PN.	USPAT	2004/08/21 20:46
13	0	6649500.URPN.	USPAT	2004/08/21 20:48
14	2	6268272.URPN.	USPAT	2004/08/21 20:48
15	9	("4443930"   "4450620"   "5510295"   "5541131"   "5607884"   "5731239"   "5759899"   "5869397"   "5924001").PN.	USPAT	2004/08/21 20:49
16	0	6255206.URPN.	USPAT	2004/08/21 20:50
17	12	("5012320"   "5023682"   "5130266"   "5268321"   "5320975"   "5648287"   "5672544"   "5741725"   "5874353"   "5880500"   "5994192"   "6001718").PN.	USPAT	2004/08/21 20:50
10	167	((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp) same (ion near implant\$8) same ((contact adj (opening hole via)) plug ((conduct\$6 metal) near via) sac (aligned adj contact)) same (gate source drain) same (sidewall spacer silicide (side adj wall))	USPAT; US-PGPUB	2004/08/21 20:52
8	205	((thermal\$4 near (process\$6 oxid\$8)) (rapid adj thermal) rto rta rtp) and (ion near implant\$8) and ((contact adj (opening hole via)) plug ((conduct\$6 metal) near via)) and (gate source drain sidewall spacer silicide (side adj wall))	EPO; JPO; DERWENT; IBM_TDB	2004/08/21 21:26